

Control charting normal variance – reflections, curiosities, and recommendations

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Outline

1 Introduction

2 Modelling

3 Two-sided EWMA charts for variance

4 Conclusions

Introduction

Aim of control charting is to detect deviations from stability

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- as fast as possible
- without too many false alarms.

Parameters characterizing stability are

- mean level,
- scale (uniformity, variance, repeatability),

• ...

Why variance?

- Ensure appropriate control limits for mean chart.
- Detect detoriated uniformity.
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Two examples from a Mask Shop

1 CD (critical dimension) uniformity:

- Measure a certain number (20 ... 200) of, e.g., lines of nominal size 200 *nm* on a single plate,
- calculate sample mean \overline{CD} and standard deviation S_{CD} ,
- chart both.
- 2 Gauge repeatibility CD-SEM (scanning electron microscope):
 - Repeat a few times (e. g., 5) the measurement of one given line,
 - calculate standard deviation S_R ,
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Modelling

Sequence $\{X_{ij}\}$, i = 1, 2, ... and j = 1, 2, ..., n > 1with $X_{ij} \sim \mathcal{N}(\mu, \sigma^2)$, independence.

The change-point model: For a certain unknown m

$$\sigma^2 = \begin{cases} \sigma_0^2 = 1 & , i < m \\ \sigma_1^2 \neq \sigma_0^2 & , i \ge m \end{cases}$$

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Pre-processing of batch data

In order to monitor σ the usual suspects are

$$\begin{split} R_{i} &= \max_{j} X_{ij} - \min_{j} X_{ij} ,\\ S_{i}^{2} &= \frac{1}{n-1} \sum_{j=1}^{n} \left(X_{ij} - \bar{X}_{i} \right)^{2} \quad , \ \bar{X}_{i} &= \frac{1}{n} \sum_{j=1}^{n} X_{ij} ,\\ S_{i} &= \sqrt{S_{i}^{2}} , \end{split}$$

$$\begin{split} & IS_i^2 = \log S_i^2 \,, \\ & abcS_i^2 = a + b \, \log(S_i^2 + c) \,. \end{split}$$

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Why log?

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- 2 It transforms scale-change into level change.
- **3** The variance of log S^2 does not depend on σ .
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Who is who in $\log S^2$ -SPC

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- Crowder & Hamilton (1992), EWMA,
- Chang & Gan (1994), EWMA,
- Chang & Gan (1995), CUSUM,

• ...

- Amin & Wilde (2000), Crosier-type CUSUM,
- Castagliola (2005), $a + b \log(S^2 + c)$ EWMA,

Short list of comparison papers

- TUPRAH & NCUBE (1987),
- Srivastava & Chow (1992),
- Lowry, Champ & Woodall (1995),
- MITTAG, STEMANN & TEWES (1998),
- Acosta-Mejía, Pignatiello Jr. & Rao (1999),
- Poetrodjojo, Abdollahian & Debnath (2002),

Further transformations

• HAWKINS (1981), $\frac{|(X-\mu_0)/\sigma_0|^{1/2} - .82218}{.34914},$ • APR (1999), $\Phi^{-1} \left[F_{\chi^2_{n-1}} \left(\frac{(n-1)S^2}{\sigma_0^2} \right) \right],$ • APR (1999), $\left[\left(S^2/\sigma_0^2 \right)^{1/3} - \left(1 - \frac{2}{9(n-1)} \right) \right] / \sqrt{\frac{2}{9(n-1)}},$ • ...

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Objects of this talk

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Two-sided EWMA charts for variance

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$$V_{i} \in \left\{S_{i}^{2}, S_{i}, R_{i}, \log S_{i}^{2}, a + b \log(S_{i}^{2} + c)\right\}$$

$$Z_{0} = z_{0} = E_{\infty}(V_{i}),$$

$$Z_{i} = (1 - \lambda) Z_{i-1} + \lambda V_{i} , i \ge 1,$$

$$L = \min\left\{i \in \mathbb{N} : Z_{i} \notin [c_{i}, c_{u}]\right\}.$$

$$Z_{i} = (1 - \lambda) z_{0} + \lambda \sum_{j=1}^{i} (1 - \lambda)^{i-j} V_{j},$$

$$(Z_{i}) = \frac{\lambda}{2 - \lambda} \left(1 - (1 - \lambda)^{2i}\right) Var(V_{i}).$$

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1 Calibrate all schemes to give $E_{\infty}(L) = 500$.

- 2 Deploy "ARL-unbiased" designs (see APR (1999)).
- $fieldsymbol{6}$ Look for "optimal" λ , that is, minimize

 $\mathcal{L}_{0.75} + \mathcal{L}_{1.25}$ and $\mathcal{L}_{0.5} + \mathcal{L}_{1.5}$, respectively,

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among $\lambda \in \{0.02, 0.03, \dots, 0.99, 1.00\}.$

(d) Optimal values for λ are:

| | | | statist | | |
|---|------|-------|---------|---------|-------------------|
| | R | S^2 | S | $ S^2 $ | abcS ² |
| $\mathcal{L}_{0.75} + \mathcal{L}_{1.25}$ | | | | 0.07 | |
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 $\begin{array}{c|c|c|c|c|c|c|c|} \hline \textbf{0} & \textbf{Optimal values for } \lambda \text{ are:} \\ \hline & statistic \\ \hline & case & R & S^2 & S & IS^2 & abcS^2 \\ \hline & \mathcal{L}_{0.75} + \mathcal{L}_{1.25} & 0.08 & 0.08 & 0.08 & 0.07 & 0.08 \\ & \mathcal{L}_{0.5} + \mathcal{L}_{1.5} & 0.23 & 0.25 & 0.24 & 0.20 & 0.27 \\ \hline \end{array}$

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Illustration for S^2 EWMA



Competition for minimal $\mathcal{L}_{0.75} + \mathcal{L}_{1.25}$



Competition for minimal $\mathcal{L}_{0.75} + \mathcal{L}_{1.25}$ II



Competition for minimal $\mathcal{L}_{0.75} + \mathcal{L}_{1.25}$ III

| ~ | statistic | | | | | | |
|------|-----------|-------------------|---------|-------|-------|--|--|
| 0 | IS^2 | abcS ² | S^2 | 5 | R | | |
| 0.4 | 4.374 | 5.251 | 6.575 | 5.143 | 5.249 | | |
| 0.5 | 5.939 | 6.389 | 7.619 | 6.374 | 6.514 | | |
| 0.6 | 8.547 | 8.409 | 9.438 | 8.459 | 8.660 | | |
| 0.7 | 13.74 | 12.59 | 13.17 | 12.63 | 12.96 | | |
| 0.75 | 18.78 | 16.56 | 16.81 | 16.67 | 17.14 | | |
| 0.8 | 27.94 | 23.92 | 23.44 | 24.04 | 24.78 | | |
| 0.9 | 96.70 | 82.24 | 76.74 | 82.26 | 84.96 | | |
| 1.0 | | | 500.000 | | | | |
| 1.1 | 90.80 | 83.53 | 81.16 | 82.43 | 86.43 | | |
| 1.2 | 30.74 | 27.27 | 25.61 | 26.61 | 27.88 | | |
| 1.25 | 22.44 | 19.61 | 18.06 | 19.04 | 19.89 | | |
| 1.3 | 17.67 | 15.26 | 13.77 | 14.73 | 15.35 | | |
| 1.4 | 12.54 | 10.60 | 9.206 | 10.12 | 10.51 | | |
| 1.5 | 9.866 | 8.190 | 6.864 | 7.740 | 8.017 | | |
| 1.6 | 8.235 | 6.735 | 5.460 | 6.295 | 6.509 | | |

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Competition for minimal $\mathcal{L}_{0.5} + \mathcal{L}_{1.5}$



Competition for minimal $\mathcal{L}_{0.5} + \mathcal{L}_{1.5}$ II



Competition for minimal $\mathcal{L}_{0.5} + \mathcal{L}_{1.5}$ III

| ~ | statistic | | | | | | |
|-----|-----------|-------------------|-------|-------|-------|--|--|
| 0 | IS^2 | abcS ² | S^2 | 5 | R | | |
| 0.3 | 2.662 | 3.120 | 4.025 | 3.114 | 3.190 | | |
| 0.4 | 3.677 | 3.763 | 4.460 | 3.824 | 3.935 | | |
| 0.5 | 5.425 | 5.014 | 5.516 | 5.113 | 5.249 | | |
| 0.6 | 8.997 | 7.678 | 7.703 | 7.736 | 7.896 | | |
| 0.7 | 18.22 | 14.79 | 13.35 | 14.47 | 14.63 | | |
| 0.8 | 49.01 | 39.91 | 33.51 | 37.94 | 37.96 | | |
| 0.9 | 174.1 | 155.7 | 137.4 | 148.8 | 148.9 | | |
| 1.0 | | 500.000 | | | | | |
| 1.1 | 136.3 | 139.3 | 138.4 | 133.0 | 137.7 | | |
| 1.2 | 37.89 | 38.31 | 38.44 | 36.39 | 38.39 | | |
| 1.3 | 17.99 | 17.30 | 17.07 | 16.57 | 17.54 | | |
| 1.4 | 11.34 | 10.40 | 10.00 | 10.02 | 10.59 | | |
| 1.5 | 8.299 | 7.327 | 6.862 | 7.072 | 7.465 | | |
| 1.6 | 6.611 | 5.674 | 5.180 | 5.466 | 5.760 | | |
| 1.7 | 5.552 | 4.664 | 4.158 | 4.474 | 4.707 | | |

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1 None of the statistics provides ARL performance that is symmetric in σ .

- 2 The log S^2 seems to be the worst approach, even beaten by R.
- 3 The newer $a + b \log(S^2 + c)$ is considerably better than $\log S^2$. But, these efforts do not really pay off.
- ④ There is no reason to deploy log based approaches at all. This is supported also by one-sided results (both EWMA and CUSUM).
- Solution For application, one should prefer S² and S. The latter is the most popular quantity at AMTC.

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Backup



Some upper variance charts

Slightly modified and shortened update of Table 5 in CHANG & GAN (1995) – the EWMA schemes are also one-sided and equipped with a lower reflecting barrier, see KNOTH (2005) for more details.

| | CUSUM-S ² | CUSUM-In S ² | EWMA- S^2 | EWMA-In S^2 |
|----------|----------------------|-------------------------|----------------|---------------------------|
| | $k_{h} = 1.285$ | $k_{h}^{\ln} = 0.309$ | $\lambda=0.15$ | $\lambda^{	ext{ln}}=0.28$ |
| σ | $h_{h} = 2.922$ | $h_{h}^{\ln} = 1.210$ | c = 2.4831 | $c^{ m ln}=1.4085$ |
| 1 | 100.0 | 100.0 | 100.0 | 100.0 |
| 1.1 | 27.9 | 30.2 | 27.9 | 30.0 |
| 1.2 | 12.8 | 13.8 | 12.9 | 13.8 |
| 1.3 | 7.75 | 8.15 | 7.86 | 8.26 |
| 1.4 | 5.47 | 5.63 | 5.57 | 5.76 |
| 1.5 | 4.22 | 4.29 | 4.30 | 4.43 |
| 2 | 2.08 | 2.11 | 2.11 | 2.22 |

Numerical handling of the sample range R

BLAND, GILBER, KAPADIA & OWEN (1966):

$$P(R/\sigma \leq r) = \int_{\infty}^{\infty} n \, \phi(x) \big(\Phi(x+r) - \Phi(x) \big)^{n-1} \, dx \, .$$



ARL integral equations and it's solution

$$\mathcal{L}(z) = 1 + \int_{c_l}^{c_u} \mathcal{L}(x) \frac{1}{\lambda} f\left(\frac{x - (1 - \lambda)z}{\lambda}\right) dx \quad , \ z \in [c_l, c_u] \,.$$

- 1 log S²: Gauss-Legendre Nyström,
- 2 others: collocation with piece-wise Chebyshev polynomials,
- 3 validated with Monte Carlo with 10^8 replicates.

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The λ hunt for minimal out-of-control ARL



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